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## The Plasma & Chemical Property Data Management System for Plasma Modeling and Simulation

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Plasma based process technology is a key technology in semiconductor manufacturing processes. Plasma Material Reaction and Plasma Chemical Data, among other things, can be used in modelling and simulation to adjust and control the gas mixture or discharge variables required for semiconductor process or materials characteristics. In this way, it increases semiconductor yields and enables precise processing[1]. Plasma Material Reaction and Plasma Chemical Data are used in various industries and studies as well as in these semiconductor fields. However, the source data management that can be used for plasma simulation and modelling haven't managed well. DCPD (Data Center for Plasma Properties) of National Fusion Research Institute has been collecting and disseminating experimental and research data related to plasma properties since 2006. We would like to introduce to plasma researchers to system for systematically providing data related to Plasma Material Reaction included a Plasma Impact and Surface Reaction Data and Plasma Chemistry Data such as Thermodynamic Data.

### REFERENCES:

[1] Alfred Grill, Cold Plasma in Materials Fabrication From Fundamentals to Applications, John Wiley & Sons, Inc, pp 1-27, 1994.